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PREPARATION AND CHARACTERIZATION OF THIN FILMS OF Tio2-PbO

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AND TiO2-Bi2O3 COMPOSITIONS

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at $\lambda = 632.8$ nm is also reported. Single and multilayer thin films of $PbTiQ_1$, $PbTi_4Q_9$ and $TiQ_2-Bi_2Q_3$ compositions have been prepared on glass and amorphous silica substrates by using the dip-coating technique. After drying and densification, these films have a high optical neutral-colored solar-energy-reflecting windows. Their use as a passive optical waveguide with a propagation of up to 4 modes quality. They have been characterized by the optical transmission technique and XPS. For certain values of their thickness they present almost flat transmission characteristics in the visible range and can be used as achromatic beam splitter or

1. Introduction

of the preparation of high optical quality single or of the substrate. In this paper, we present results Bi₂O₃ compositions obtained by dip-coating. multilayer thin films of TiO2-PbO and TiO2surfaces with coatings on either one or both faces techniques. The low processing temperatures may it offers potential advantages over traditiona the process also allows the fabrication of large particularly facilitate their use with semiconductor devices has received much attention in recent years and integrated optical devices. On the other hand The sol-gel method appears very attractive since The fabrication of high quality thin films and

energy-reflecting glasses and passive optical waveachromatic beam splitters, neutral-colored solarcuss possible applications for the realization of as some preliminary XPS results. Finally, we disshow their principal optical characteristics as wel ditions required to obtain the films. Then, we the precursors, the sols and the experimental con-We first describe in detail the preparation of

2. Experimental procedures

TiO₂-PbO and TiO₂-Bi₂O₃ materials have not

portant electrical ceramics and as thin films may prepared via conventional processing procedures. optical devices. be useful for the development of electronic and However they are the basic constituents of improved to be important technological systems when

2.1. Precursor and sol preparations of TiO,-PbO compositions [1]

ethanol and water (2:1 ratio) with 0.002 mol PbTiO₃ was reported after firing at 600°C. after drying at 34°C for 2-3 weeks. Tetragonal HNO3/mol water added. Gelation occurred in a the water of hydrolysis as a solution of methoxymethoxyethanol (1:7 ratio volume) introducing were prepared by dissolving this complex in poxide Ti(OC3H7)4. The synthesis process was methoxyethanol C₃H₈O₂ with titanium isoproreaction of lead acetate Pb(C2H3O2)2 dissolved in was made by Gurkovich and Blum [2] through the highly viscous with high moisture sensitivity. Sols rather complicated and the final product was few minutes and transparent gels were obtained The first preparation of a PbTiO3 precursor

through gas chromatography, the occurrence of an modified by Budd et al. [3,4] who recognized The precursor preparation process was later

and methoxyethanol: exchange reaction between the titanium alkoxide

$$Ti(OR')_4 + 4(ROH) \rightarrow Ti(RO)_4 \rightarrow 4R'OH,$$
 (1)
with $R' \equiv iC_3H_7$ and $R \equiv CH_3OCH_2CH_2$.

increasing with the water concentration and pH. gelation occurred in a few minutes with a rate [PbTiO₃] ratio lower than 1.5. For higher ratios ethanol. Stable sols were obtained for a [H2O]/ solution of water-catalyst (acid or base)-methoxyan equal volume of the stock solution with a thin film preparation were prepared by combining vacuum distillations. Sols for gel formation and acetate, reacted, and concentrated by repeated way at 125°C methoxyethanol The titanium methoxyethoxide prepared in this was then combined with solution of dehydrated lead a 2-

chelating ligand and stabilizing agent [5-7]. The by the exothermic reaction [8]: preparation of the complex alkoxide is described Ti(OPr'), by acetylacetone AcacH, a rather strong chemical modification of titanium isopropoxide dense material in film form. It is based on the cursor sols, and particularly useful for obtaining We propose an easier method to prepare pre-

$$Ti(OPr^{i})_{4} + 2AcacH \rightarrow Ti(OPr^{i})_{2}(acac)_{2}$$
$$+ 2(Pr^{i}OH).$$

(2)

(concentration 720 g/l) is then added and stirred for 30 min. This sol does not exhibit gelation or days, indicating either an evolution of the Ti comprecipitation for at least 6 months. However, its precursor sols can be mixed in any proportion to plexation or a change in the particle size. Both color changes from clear yellow to orange in a few A solution of lead acetate Pb(OAc)2 in acetic acid for 30 min until its temperature decreases to 25°C The yellow and homogeneous solution is mixed

Typical composition for the preparation of PbTiO3 PbTi₄O₉ sol and

Product	Pr'OH	AcacH	Ti(OPri),	Pb acetate	pΗ
	回)	<u>m</u>)	(ml)	solution	
$PbTiO_3$	40	u	4	7.24	1.4
PbTi₄O ₉	40	w	4	1.81	5.7

Pro Table 2 Typical composition for the preparation of TiO2-Bi2O3 sol

)H AcacH Ti(OPr'),	cacH Ti(OPr')	4 Bi nitrate	ΡH
		solution	
(п		(ml)	
TiO ₂ -Bi ₂ O ₃ 30 1.8 2.5 1.9	3 2.5	1.9	0.86

prepare lead-titanate material of other compositions (table 1).

2.2. Precursor and sol preparations of TiO2-Bi2O2 composition

a similar procedure. However the bismuth sols in order to prepare other compositions. Table 2 were prepared by mixing Bi(NO3)3+ 5H2O in acetic shows a typical composition. the precursor sol can be mixed in any proportion acid with a concentration of 665 g/l. Once again The preparation of the precursors and sols in this system is based on the same ideas and follows

2.3. Film preparation

cess can be repeated if thicker films are desired. about I µm. with up to 15 coatings yielding a thickness of Good optical characteristics have been obtained with Fabry-Perrot interferometry, were found to cm/min. After each coating procedure, the films (typically 60 nm for 10 cm/min). The whole probe roughly proportional to the withdrawal speed densify them. The thickness of the films, measured were dried and heat treated to 500 °C in order to Usually, both faces of the substrates are coated. either on common glass microscope slides or pure The withdrawal speed was typically 4 to 15 amorphous silica substrates previously cleaned. Thin films have been obtained by dip-coating

ing their optical thickness, almost flat reflection good candidates for reflective coatings. By tailorsorption in the visible range. Therefore they are about 2.15 and exhibit practically no optical abvisible range. and transmission properties can be achieved in the These films have an index of refraction of

Thin film characterization

using the well known ellipsometric relations. The thickness and index of refraction of the films have been determined by best fitting the transmission spectra to theoretical ones calculated

spectrum has an almost flat characteristic in the mission (see also fig. 3). Their index of refraction films are practically densified around 450 °C and have an index of refraction of 2.12 at 540 nm. The (1 dip) as a function of the heat treatment. The coated on each side by a thin layer of TiO2-Bi2O3 mission spectrum of a 1 mm thick glass substrate is around 2.10. results with however slightly larger optical transfrom 53 to 65%. PbTi₄O₉ coatings [1] show similar visible region with a transmission value varying Figure 1 shows examples of the visible trans-

into the film during the heat treatment. The specis probably due to Na diffusion from the substrate shown in fig. 2 (McPherson ESCA-36 Al Ka PbTi₄O₉ thin films coated on glass substrates are and C. The last impurity is mainly encountered amount of impurity is larger near the substrate the films have small Na contaminations; the 1486.6 eV excitation). The results indicate that all tra show also a small contamination with S, Ca (see curves b, c and d) indicating that its presence Preliminary XPS analysis of PbTiO3 and

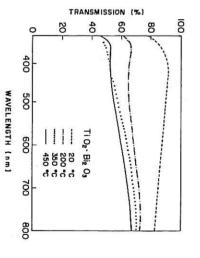


Fig. 1. Transmission spectra of TiO₂-Bi₂O₃ thin film coated on both faces of a glass substrate as a function of the heat treatment.

are not chemically homogeneous through their 17 min Ar sputtering. This indicates that the films discarded. The average atomic ratio Pb/Ti is 0.65 group during the densification process can not be however, an incomplete elimination of the carbon near the surface indicating probably a superficial contamination due to a poor vacuum (10⁻⁷ Torr); This last value decreases to 0.16 ± 0.04 after 10 kV ± 0.15 for PbTiO₃ and 0.33 ± 0.07 for PbTi₄O₉. thickness and are richer in lead near their external

slightly (138.4 to 138.9 eV) and its value is somepure PbO and PbO₂. After Ar sputtering (see curve d) both Pb 4f^{7/2} and Pb 4f^{5/2} start to split what intermediary between the lines observed however, the position of the Pb(4f $^{7/2}$) line varies 458.5 ± 0.3 eV is consistent with the value 4+; lower valence. showing a possible reduction of Pb into oxide of The energy position of the Ti 2p3/2 line ō

Applications

candidates for various applications. their ease of fabrication make them interesting The good optical quality of these thin films and

4.1. Preparation of achromatic beam splitters and neutral-colored solar-energy-reflecting windows

also be obtained by using mixed SiO₂-TiO₂-PbO consequently an increase of the transmission can value. It is worth noting that coating on one side index of refraction and gives a lower transmission absence of Na diffusion, the coating on pure nm) and TiO_2 -Bi₂O₃ (t = 63 nm). Because of the spectral region. Figure 3 shows some results obing optical characteristics can be obtained using a only will reduce the reflection by a factor 2. On amorphous silica substrate has a slightly higher tained with PbTiO₃ (t = 72 nm), PbTi₄O₉ (t = 55 m) tion characteristics can be achieved in the visible faces of a glass substrate. By carefully selecting single dip-coating procedure either on one or both the other hand a reduction of the reflection and the value $n \cdot t$, almost flat transmission and reflec-Because of their high refractive index, interest-

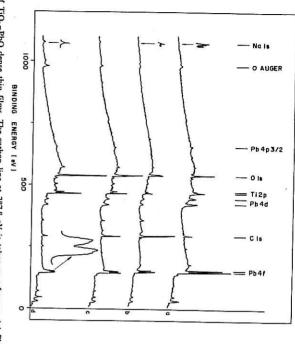


Fig. 2. XPS spectra of TiO_2 -PbO dense thin films. The carbon line at 287.8 eV is taken as reference. (a) PbTiO₃, $t \approx 70 \text{ nm}$; (b) PbTi₄O₉, $t \approx 55 \text{ nm}$; (c) Same as (b) after 2 min 10 kv Ar sputtering; (d) Same as (b) after 17 min 10 kv Ar sputtering.

or Bi₂O₃ precursors which gives films with lower indexes of refraction.

Since these films do not have absorption in the visible range, they are good candidates for achromatic beam splitters and neutral-colored

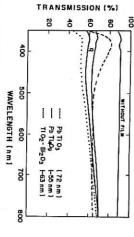


Fig. 3. Transmission spectra of dense films coated on both sides of a glass substrate. ———, PbTiQ₀, t = 72 nm, heat treated at 460°C for 15 min. ———, PbTi₄Q₀, t = 55 nm, n = 2.10, heat treated at 460°C for 15 min. — $\frac{4}{10}$, Same as above coated on amorphous quartz substrate, t = 51 nm, n = 2.19 heat treated at 460°C for 15 min., TiQ₂-Bi₂Q₃,

t = 63 nm, n = 2.12, heat treated at 450 °C for 1 h.

solar-energy-reflecting windows. They should present considerable advantages compared with sun shielding glass in which the solar energy is absorbed or stoped in the glass.

by choosing an adequate sol composition optical characteristics similar to Schott type 411, 412 and 413 can be easily obtained.

4.2. Preparation and characterization of passive planar waveguide

The fabrication of passive optical devices using the sol-gel method is simple and inexpensive. It has great advantages since the method allows the choice of index of refraction and the thickness of the layers. Hermann and Wildmann [9] have shown the feasibility of the method by fabricating planar optical waveguides using SiO₂-TiO₂ Lipicoat

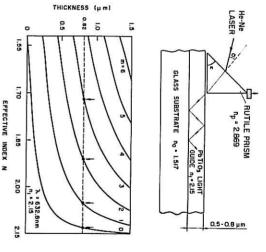


Fig. 4. (Top) Prism coupler method to couple He-Ne laser light beam to a $PoTI_0O_0$ planar waveguide. (Bottom) Dispersion relation for a $PoTI_0O_0$ waveguide ($n_1 = 2.15$ at $\lambda = 623.8$ nm) deposition on a glass substrate ($n_0 = 1.517$) showing the various effective modes of propagation obtained as a function of the film thickness. The dashed line refers to a film 0.82 μ m thick (15 layers) measured experimentally (see table 3).

Merck solution. Using a rutile prism coupler, we successfully coupled a He-Ne laser beam to a thin planar PbTi₄O₉ film 0.82 μ m thick deposited on a common glass substrate. The upper part of fig. 4 shows schematically the experimental set-up and the lower part shows the dispersion relation of the films thickness versus the effective index of refraction, N, for the propagation of TE modes m = 0 to m = 6 calculated for a thin film of index of refraction $n_1 = 2.15$ [10]:

$$N = n_{\rm p} \sin(\epsilon + \arcsin((\sin \alpha)/n_{\rm p})), \tag{3}$$

where $n_p = 2.869$ and $\epsilon = 42.2^\circ$ are the index of refraction and the angle of the rutile coupling prism, respectively, and α is the angle of incidence of the He-Ne laser light on the prism. Four propagation modes have been observed (TE₀, TE₁, TE₂ and TE₃). The N_m values calculated with the relation (3) are in good agreement, within 1.5%, with those derived from fig. 4.

a new field of application as the layers were neous through their thickness. No measurement have been done yet with TiO2-Bi2O3. passive waveguide appear much more homogefilms, such as those used for the preparation of a very thin films (fig. 2) probably affects only a very tion of the Pb/Ti atomic ratio observed by XPS in with a sharp variation at the interface. The variathe index of refraction of the film and substrate curves were done by assuming constant values of theoretical derivation of N_m and the dispersion derived films. It is interesting to note that the firm the good optical quality of these lead-titanate tion, filtration and clean room facilities and conprepared without special substrate cleaning soluthin layer near the film substrate interface. Thicker These results are extremely promising and open

[13]. tapered and lens-like waveguides. varying speeds, Hewak and Lit [14], fabricated requires an engraved pattern. Recently, using a may function as an input or output grating coustamper followed by baking at 500°C. The replica and more recently by Tohge et al. for SiO2 ZLI 1686 Merck) by Lukosz and co-workers [11,12] waveguides would be another promising possibilto fabricate surface-relief gratings and channel draw a microprocessor-controlled dipping arm to withcal memory disk or any other optical device which pler, a Bragg reflector, the pregrooves of an optifilm against an aluminized reflective grating or and resistant SiO2-TiO2 sol-gel films (Liquicoat ij Embossing techniques used in integrated optics This technique was first developed for hard The technique involves the pressing of a dry SiO₂-TiO₂ film from the solution with

The successful and easy preparation of thin lead titanate films of high optical quality com-

Table 3 Experimental values of α_m and calculated values of N_m (see also fig. 4)

-0°33′	TE ₀ 18°38' 2.15 TE ₁ 11°09' 2.07	$TE_m \alpha_m \ (\pm 5') N_m \ (\pm 0.02)$ (from rel. (3))
1.90	2.12	1.02) N_m
1.70	2.04	:l. (3)) (from fig. 4)

any doubt good candidates for future research and bined with their high refractive index are without applications in this optical field.

5. Conclusion

Thin films have been prepared in the system TiO₂-PbO and TiO₂-Bi₂O₃ using a dip-coating technique.

acteristics have not been yet studied. ing windows. The chemical and mechanical charsplitters and neutral-colored solar-energy-reflectcandidates for the preparation of achromatic beam region, suggesting that these films are good and reflection characteristics in the visible spectral have obtained almost flat spectral transmission easy to prepare. By adjusting their thickness we These films have good optical quality and are

observed. Ti ions are compatible with a valence 4 tween PbO and PbO2. but Pb shows a tendency to be intermediary be-Contamination with Na, C, Ca, and S has been analysis of TiO2-PbO films shows, however, that they can also be used for the realization of passive planar waveguides, with possible applications in the field of integrated optics. Preliminary XPS thought by measuring their optical characteristics. the layers are not as homogeneous as it was Using thicker films we have demonstrated that

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